

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Takahiro KISHIOKA et al.

Application No.: 10/530,349

Filed: April 27, 2005

Docket No.: 123418

For: COMPOSITION FOR FORMING ANTI-REFLECTIVE COATING FOR USE IN  
LITHOGRAPHY

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

Pursuant to 37 CFR §1.56, the attention of the Patent and Trademark Office is hereby directed to the references listed on the attached PTO-1449. Unless otherwise indicated herein, one copy of each reference is attached. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the references be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

- 1. This Information Disclosure Statement is being filed before the mailing date of a first Office Action on the merits in the present application. No certification or fee is required.
- 2. One or more reference cited herein was cited in a counterpart foreign application. An English language version of the foreign search report is attached for the Examiner's information. See References 1, 2 and 6-12.
- 3. In accordance with 37 CFR §1.98(a)(2)(ii), copies of any U.S. patents and patent application publications are not attached.
- 4. An English language Abstract of one or more non-English language reference is attached hereto. See Reference 8.
- 5. A computer-generated English language translation of one or more Japanese Patent Publication cited herein has been obtained from the website of the Japanese Patent Office ([<http://www.jpo.go.jp>]), and is attached, but has not been reviewed for accuracy. See Reference 8.

6. Reference 3 corresponds to Reference 10. Reference 4 corresponds to Reference 11. Reference 5 corresponds to Reference 12.

Respectfully submitted,



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Form PTO-1449 (REV. 1/06)		US Dept. of Commerce PATENT & TRADEMARK OFFICE	ATTY DOCKET NO. 123418	APPLICATION NO. 10/530,349
INFORMATION DISCLOSURE STATEMENT  (Use several sheets if necessary)		APPLICANTS Takahiro KISHIOKA et al.		
		FILING DATE April 27, 2005		
U.S. PATENT DOCUMENTS				
Examiner Initials	Cite No.	Document Number	Date	Name
	1.	5,250,591	10/05/1993	Ryuichi FUJII et al
	2.	4,874,860	10/17/1989	Bernd GALLENKAMP et al
	3.	6,306,502 B1	10/23/2001	Hiroshi FUKUSHIMA et al
	4.	6,440,568 B1	08/27/2002	Hisayuki KAYANOKI et al
	5.	2005/0175927 A1	08/11/2005	Takahiro KISHIOKA et al
FOREIGN PATENT DOCUMENTS				
Examiner Initials	Cite No.	Document Number	Date	Country
	6.	EP 0 098 006	01/11/1984	EUROPE
	7.	GB 1 286 684	08/23/1972	GREAT BRITAIN
	8.	JP-A-05-255282	10/05/1993	JAPAN
	9.	FR 2 629 462	10/06/1989	FRANCE
	10.	EP 0 869 154 A1	10/07/1998	EUROPE
	11.	EP 0 922 971 A1	06/16/1999	EUROPE
	12.	EP 1 542 075 A1	06/15/2005	EUROPE
OTHER DOCUMENTS				
Examiner Initials	Cite No.	(Including Author, Title, Date, Pertinent Pages, etc.)		
	13.	Dirk SCHMALJOHANN et al., "Design Strategies for 157 nm Single-Layer Photoresists: Lithographic Evaluation of a Poly( $\alpha$ -trifluoromethyl vinyl alcohol) Copolymer", <i>Advances in Resist Technology and Processing XVII</i> , Proceedings of SPIE, Vol. 3999 pp 330-334 (2000)		
	14.	Michael K. CRAWFORD et al., "New materials for 157 nm Photoresists: Characterization and Properties", <i>Advances in Resist Technology and Processing XVII</i> , Proceedings of SPIE, Vol. 3999 pp 357-364 (2000)		
	15.	Kyle PATTERSON et al., "Polymers for 157 nm Photoresist Applications: A Progress Report", <i>Advances in Resist Technology and Processing XVII</i> , Proceedings of SPIE, Vol. 3999 pp 365-374 (2000)		
Examiner: Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.				